

A schematic diagram of a plasma processing apparatus. The main chamber (1) contains a substrate (2) mounted on a pedestal (3). The pedestal has three vertical support columns (3a, 3b, 3c) and a central column (3d). The substrate is tilted at an angle. A gas inlet (4) is located at the top right. A gas outlet (5) is at the bottom left. A power supply (6) is connected to the substrate via a cable (7) and a switch (9). The power supply (6) is also connected to the pedestal (3) via a cable (8) and a switch (10). A control unit (11) is connected to the power supply (6) and the pedestal (3). A coordinate system (X, Y, Z) is shown at the bottom right.

FIG. 3

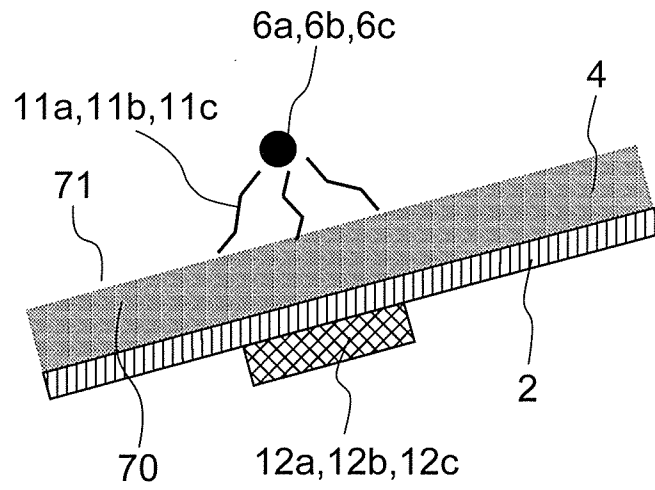


FIG. 4

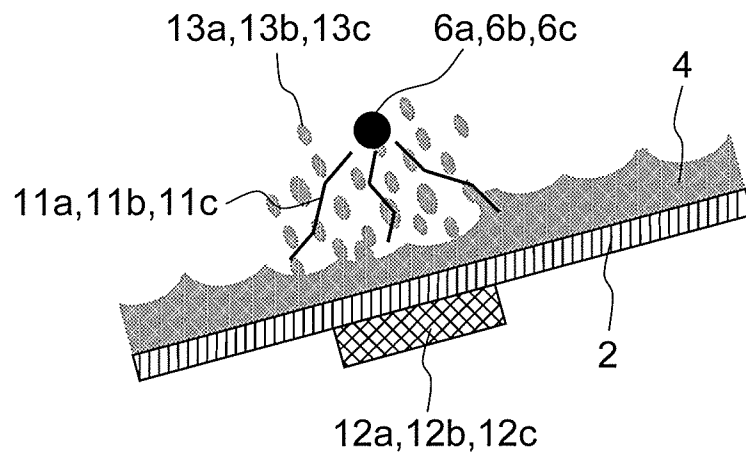


FIG. 5

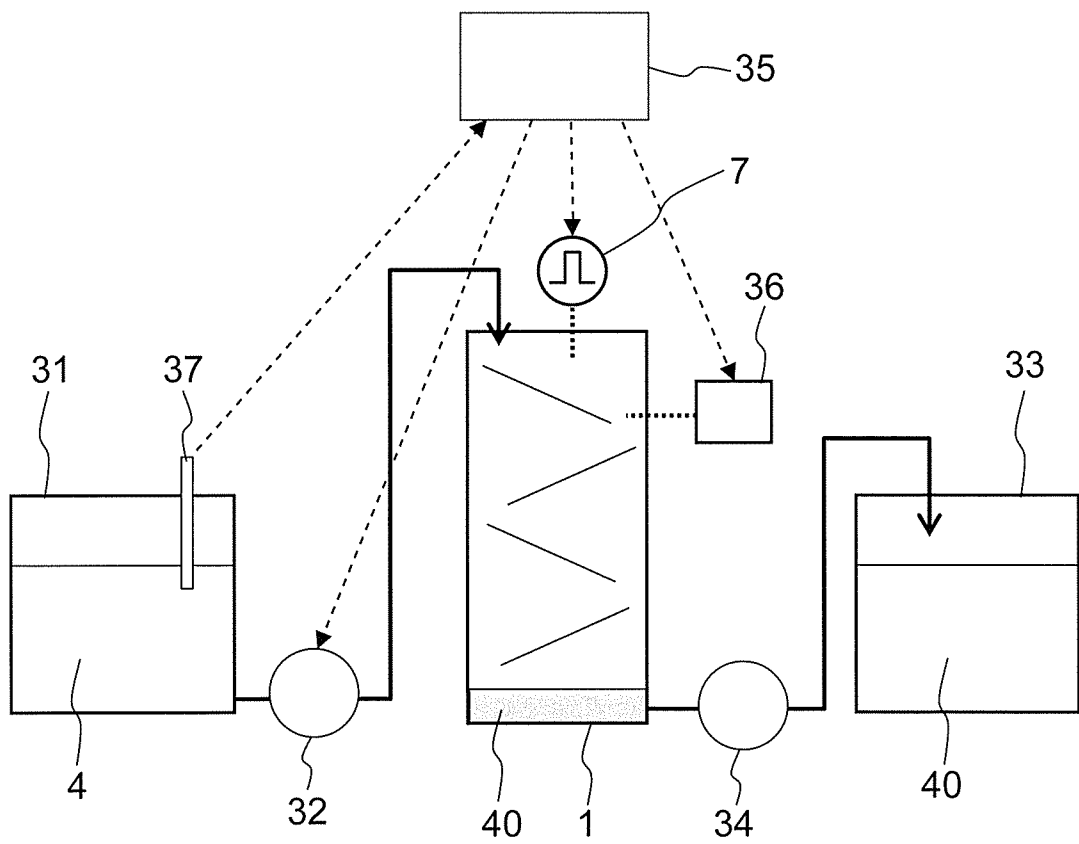


FIG. 6

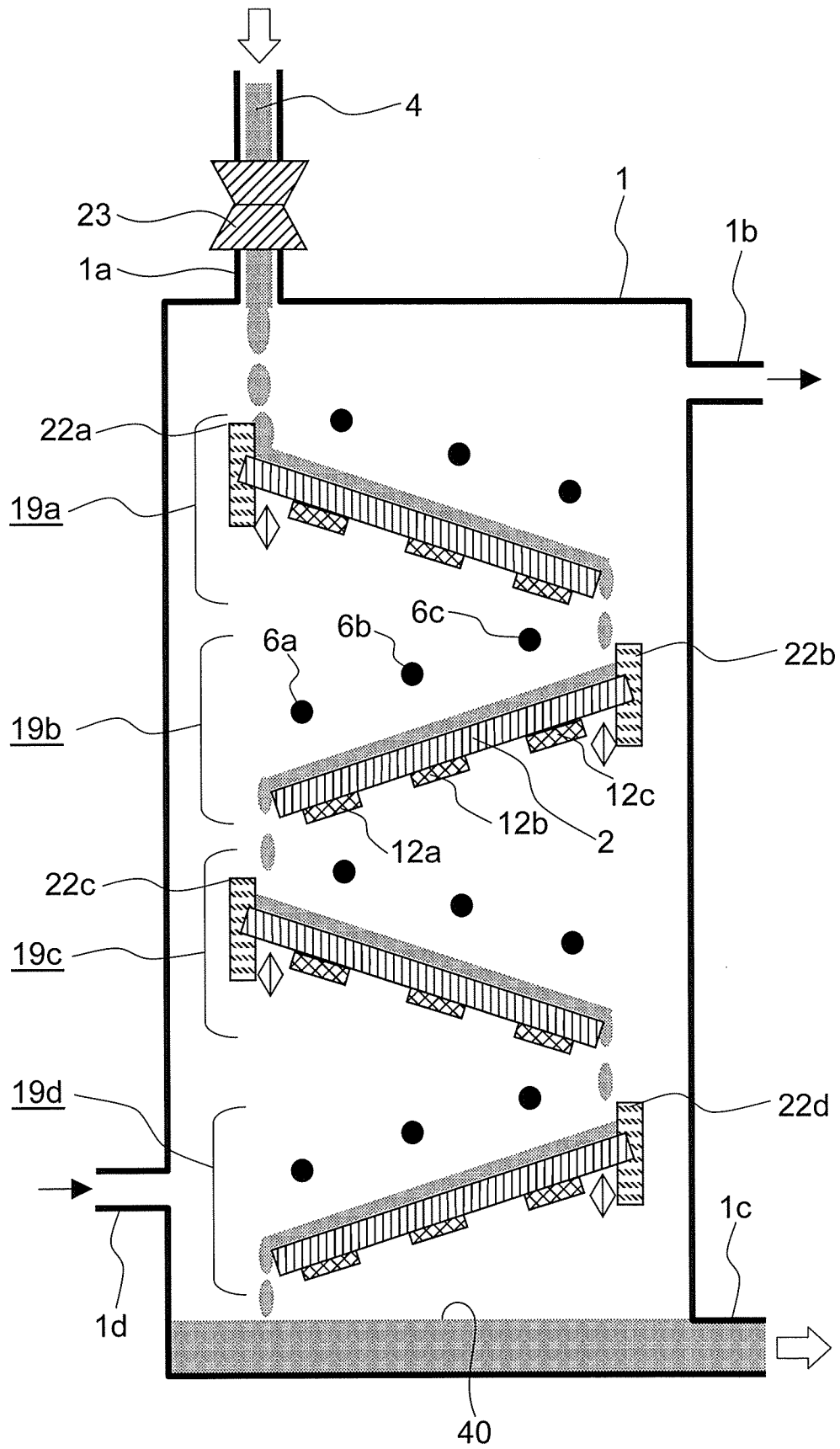


FIG. 7

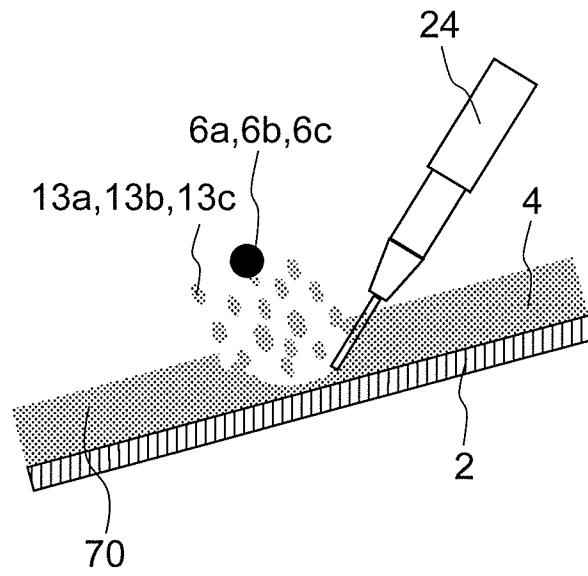


FIG. 8

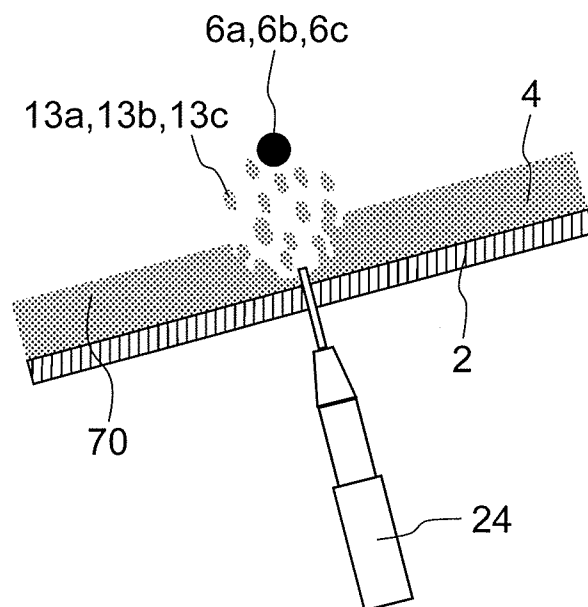


FIG. 9

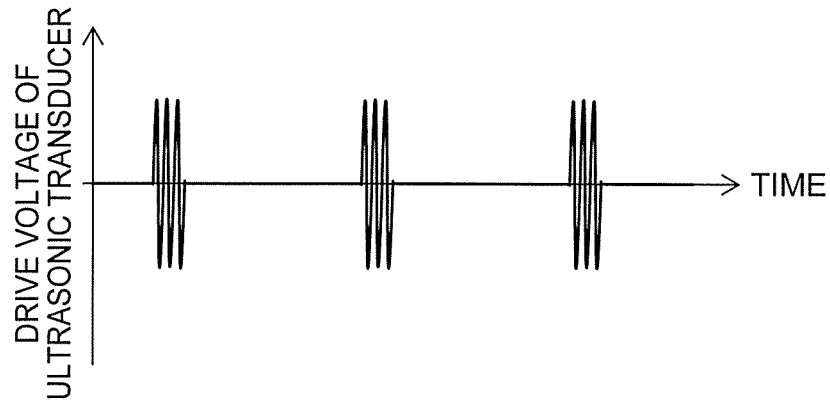


FIG. 10

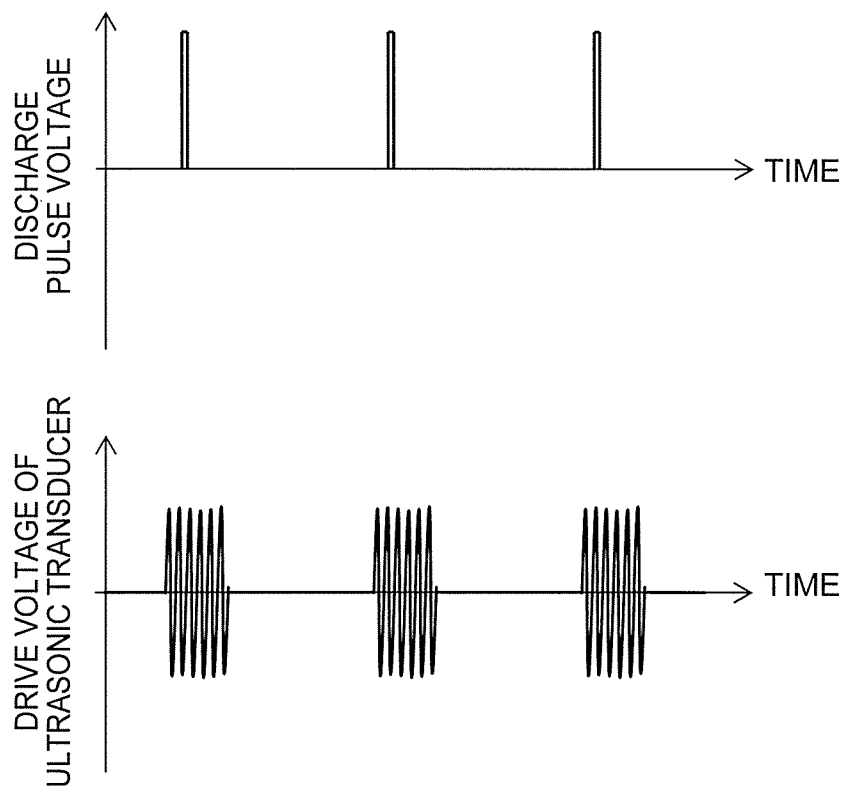


FIG. 11

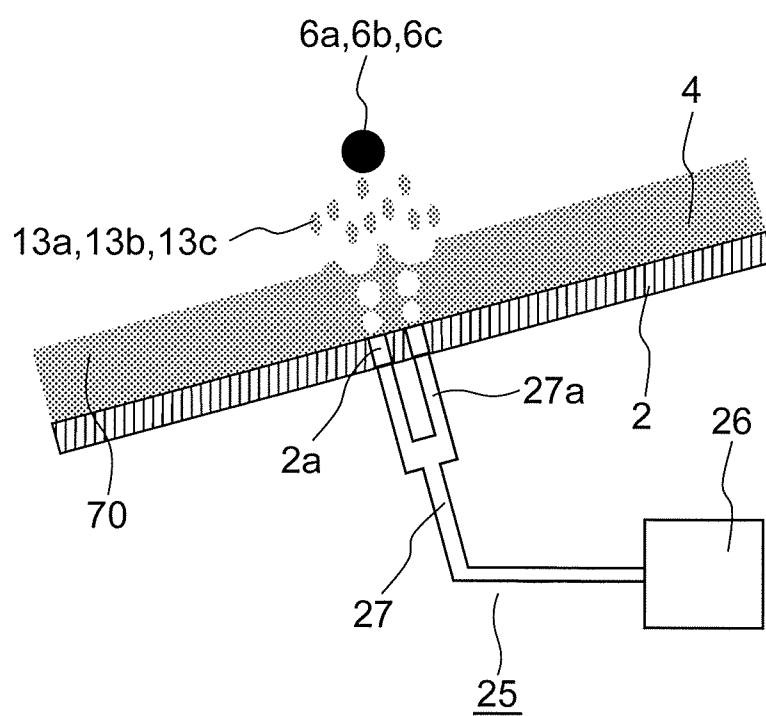


FIG. 12

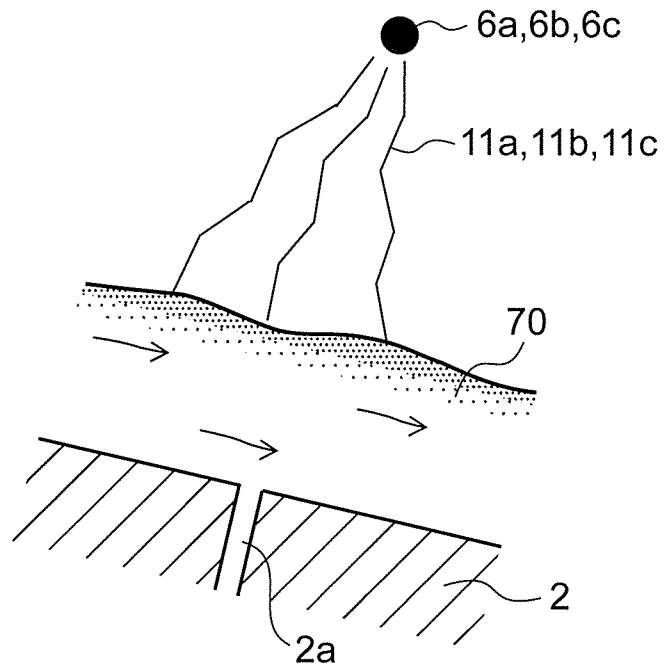


FIG. 13

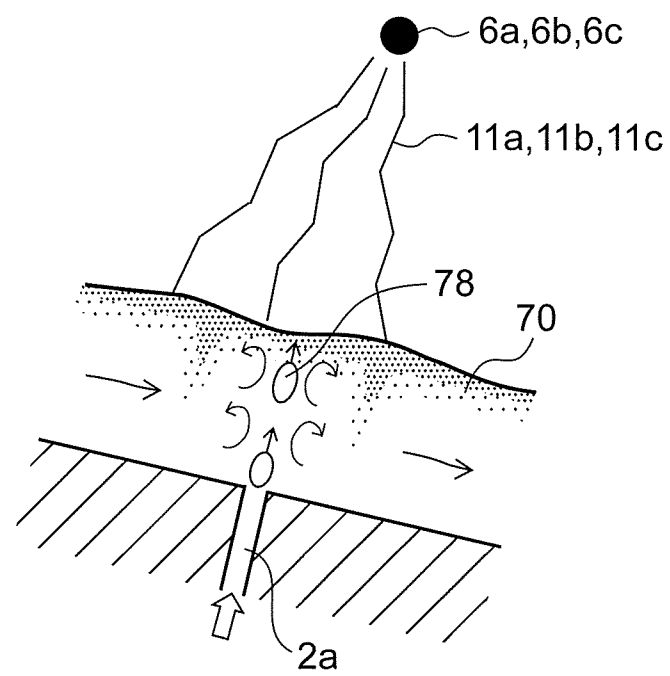


FIG. 14

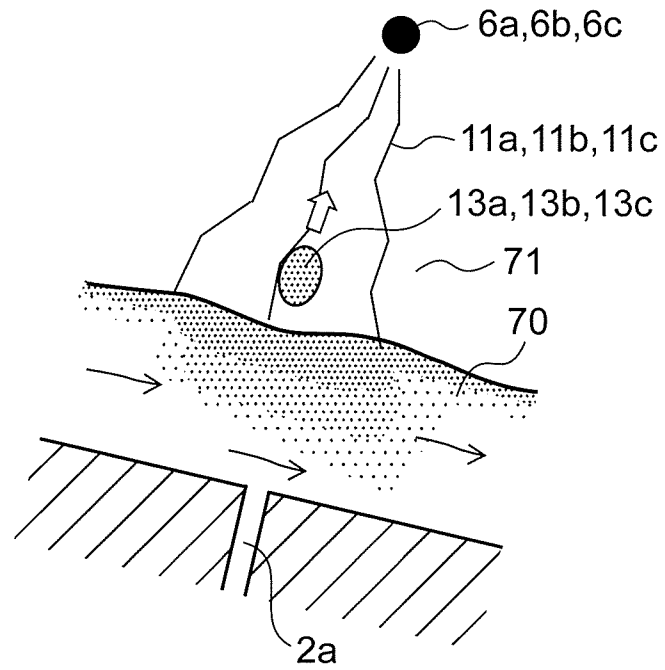


FIG. 15

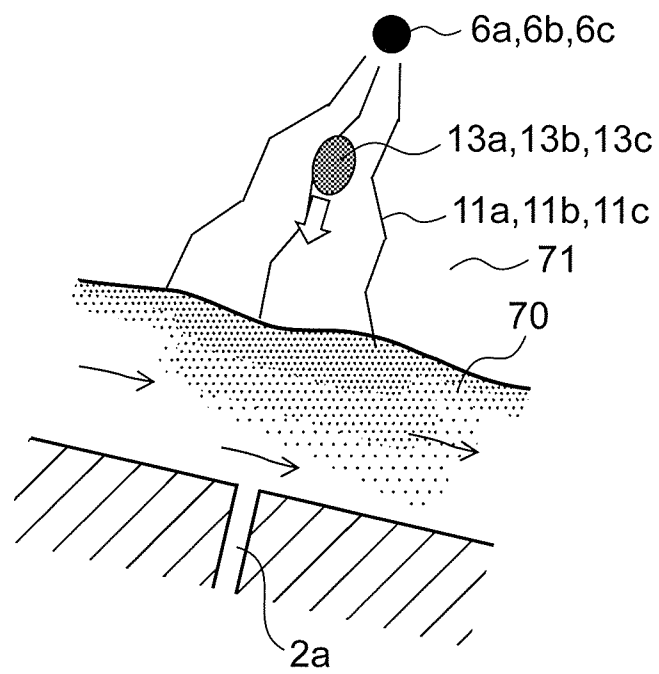


FIG. 16

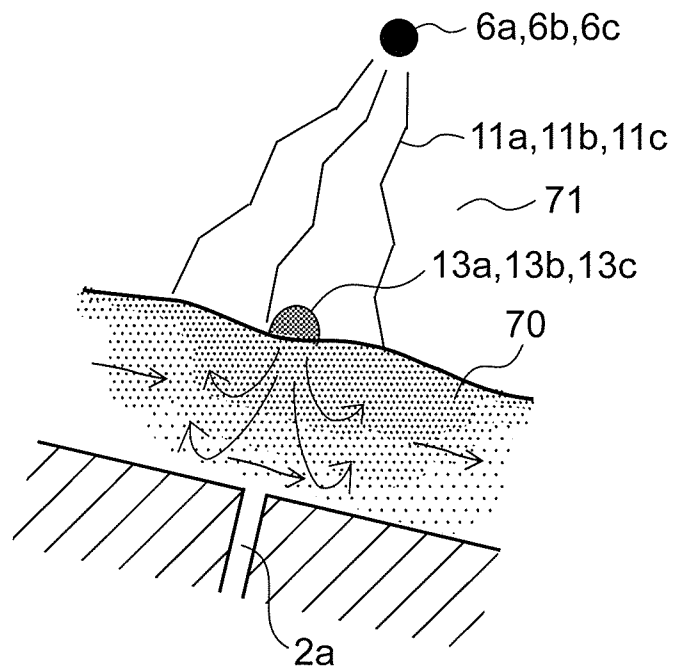


FIG. 17

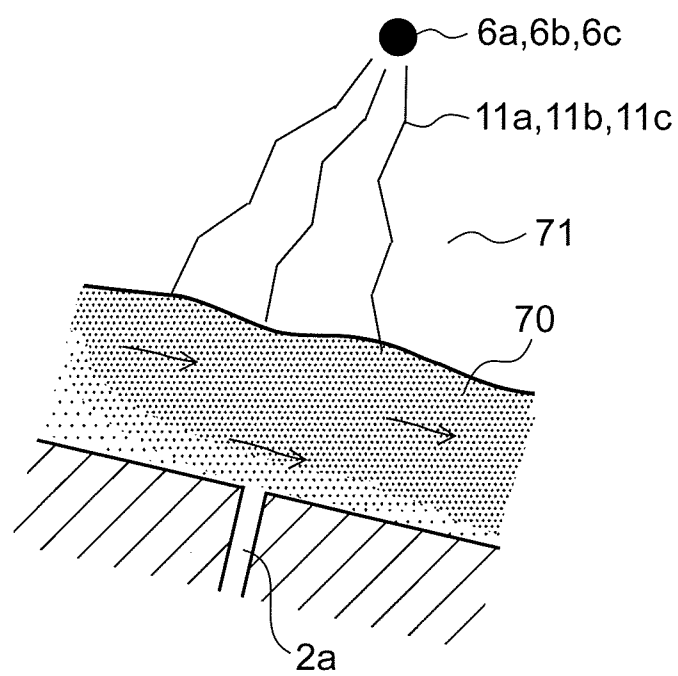


FIG. 18

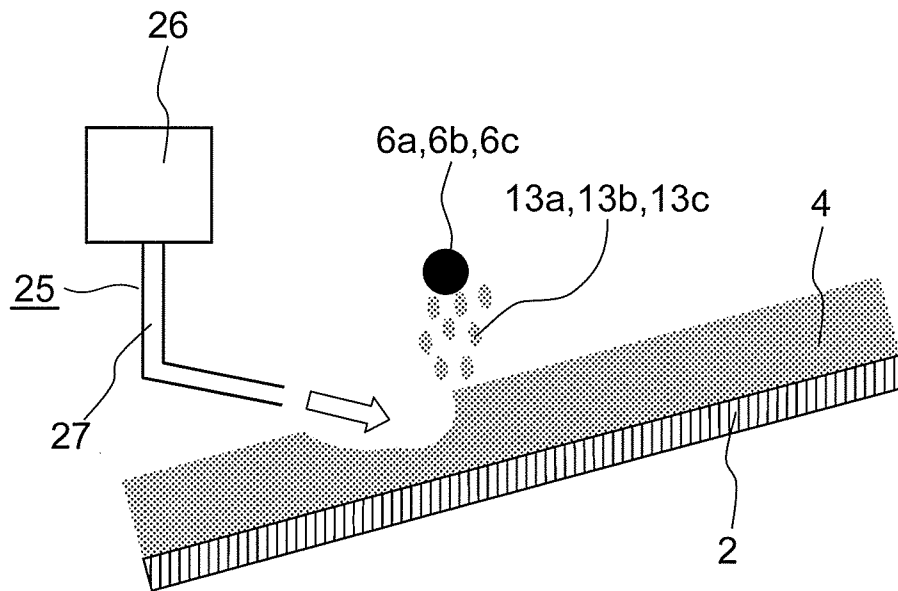


FIG. 19

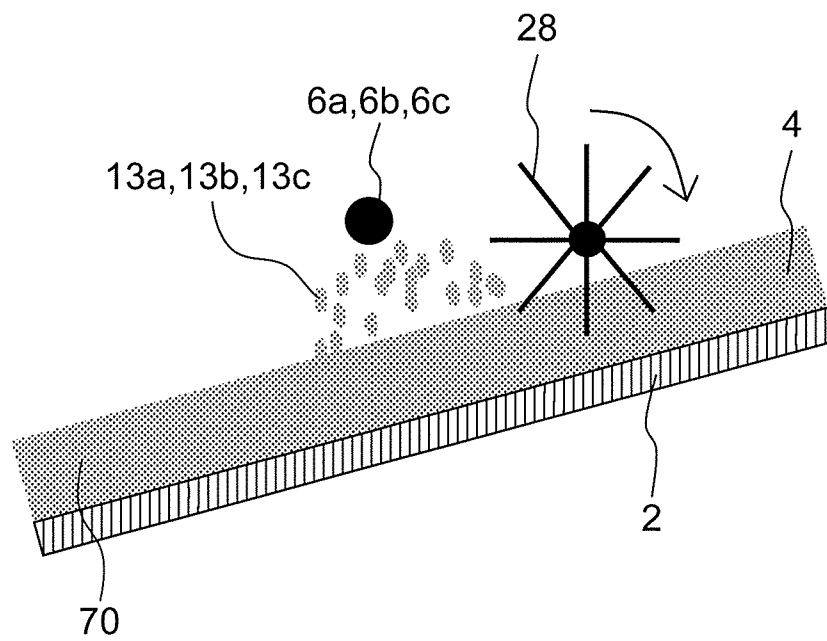


FIG. 20

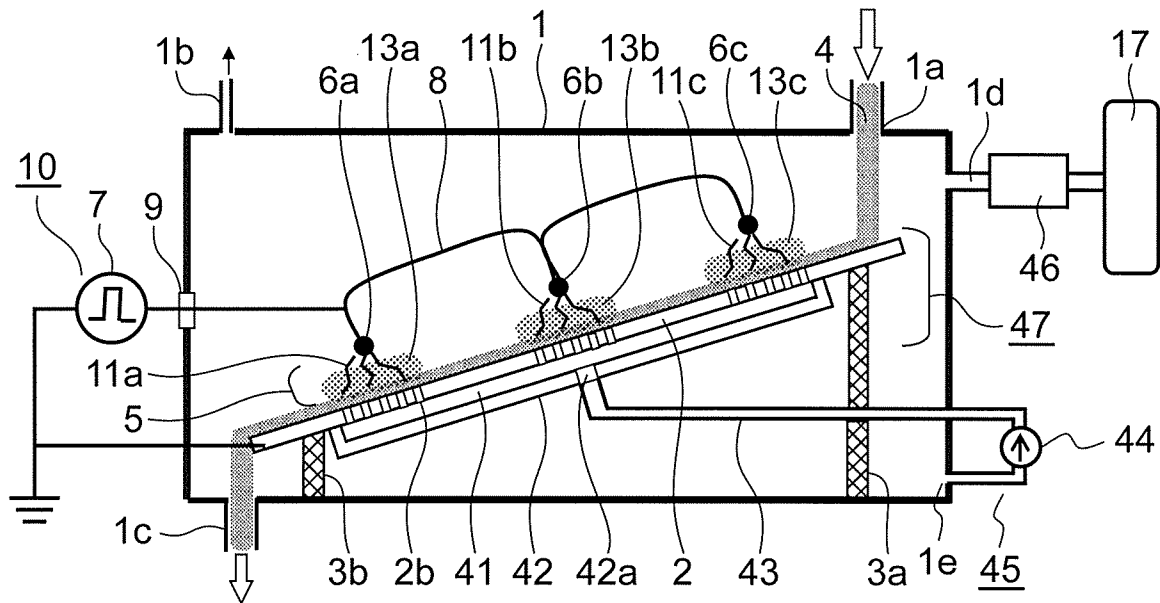


FIG. 21

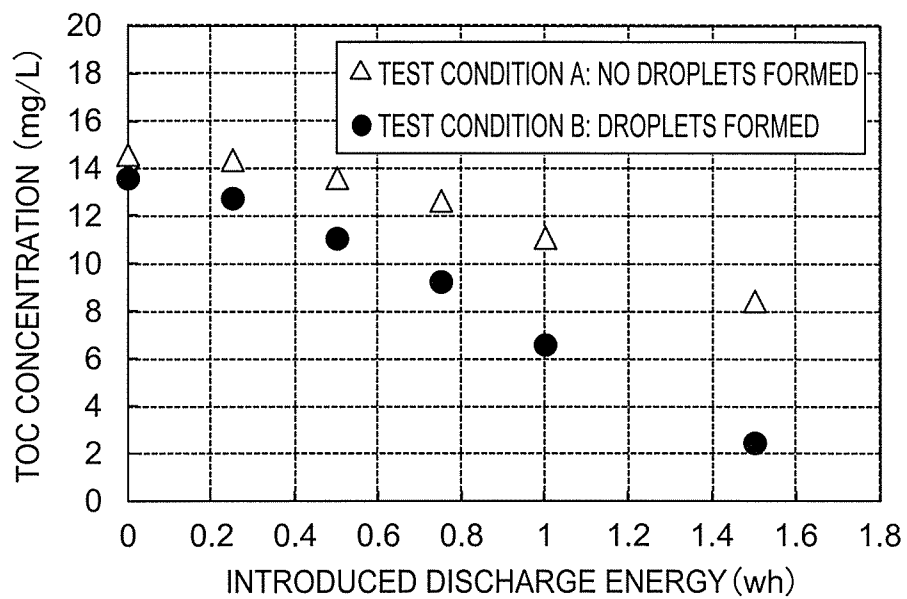


FIG. 22

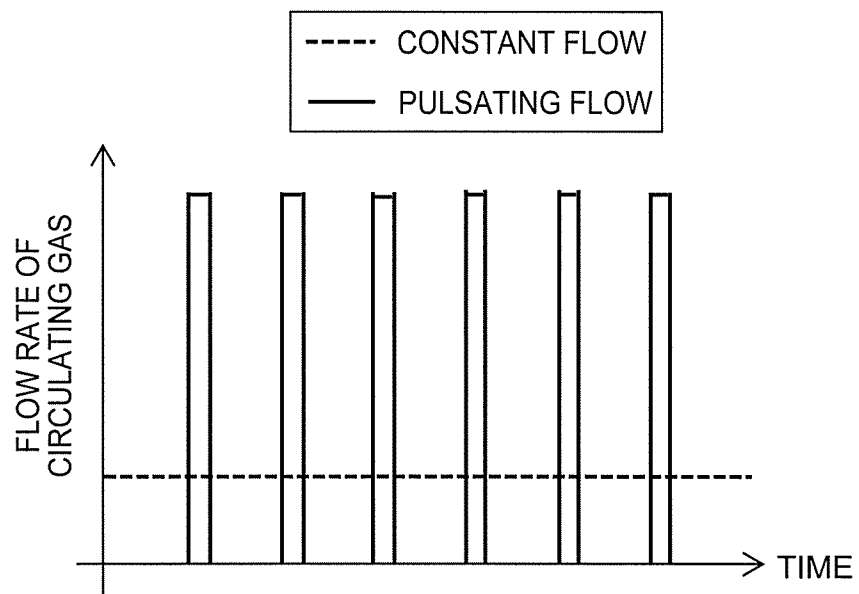


FIG. 23

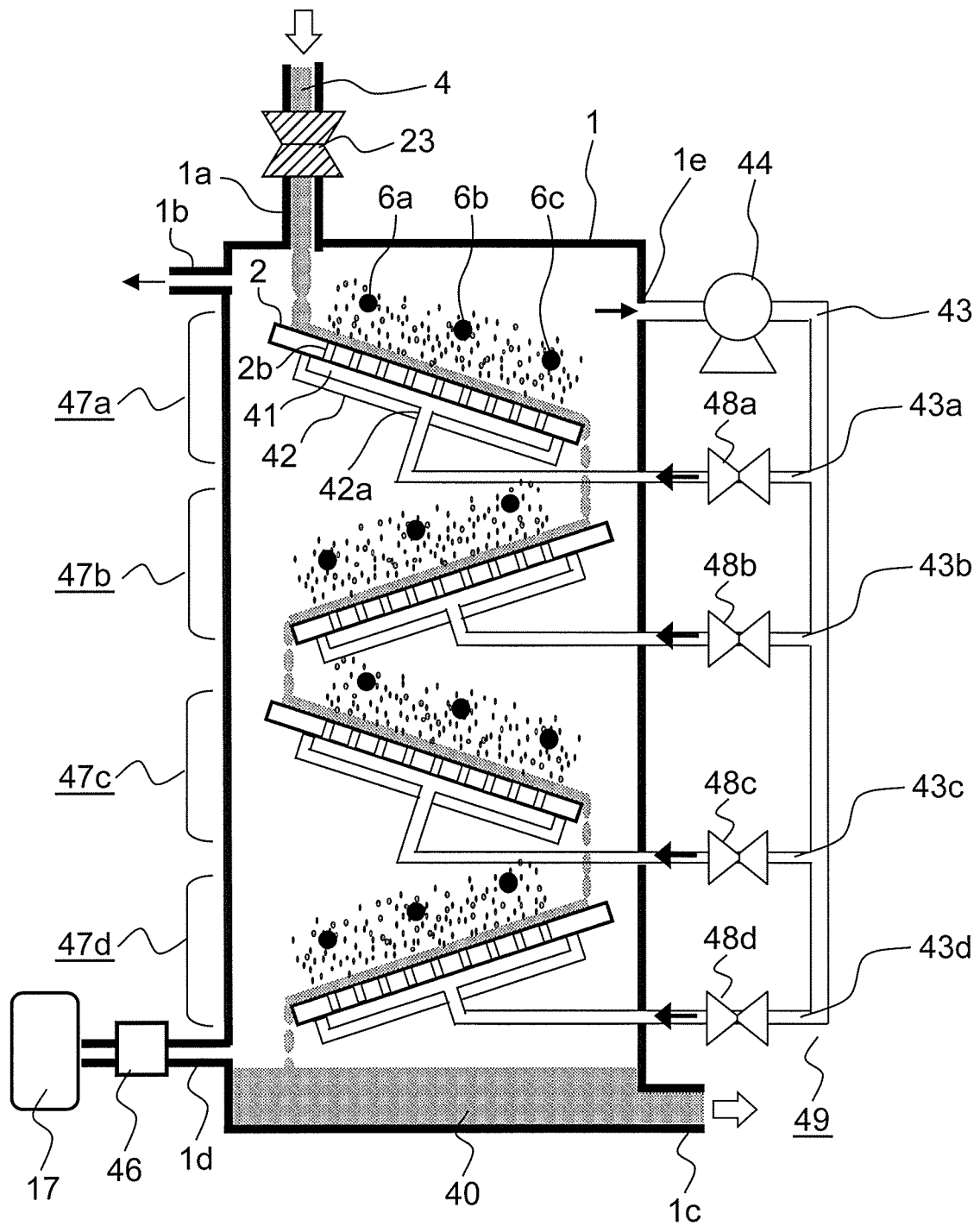


FIG. 24

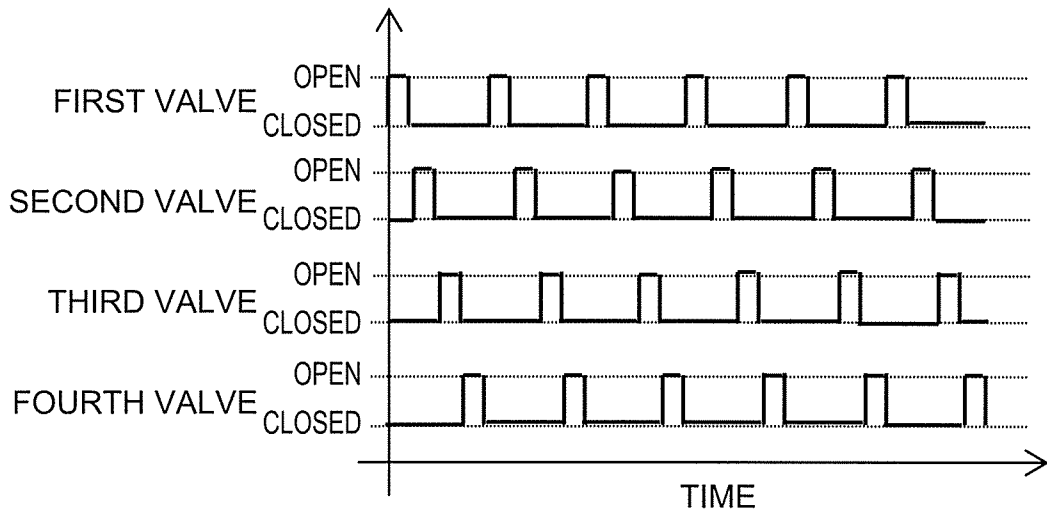


FIG. 25

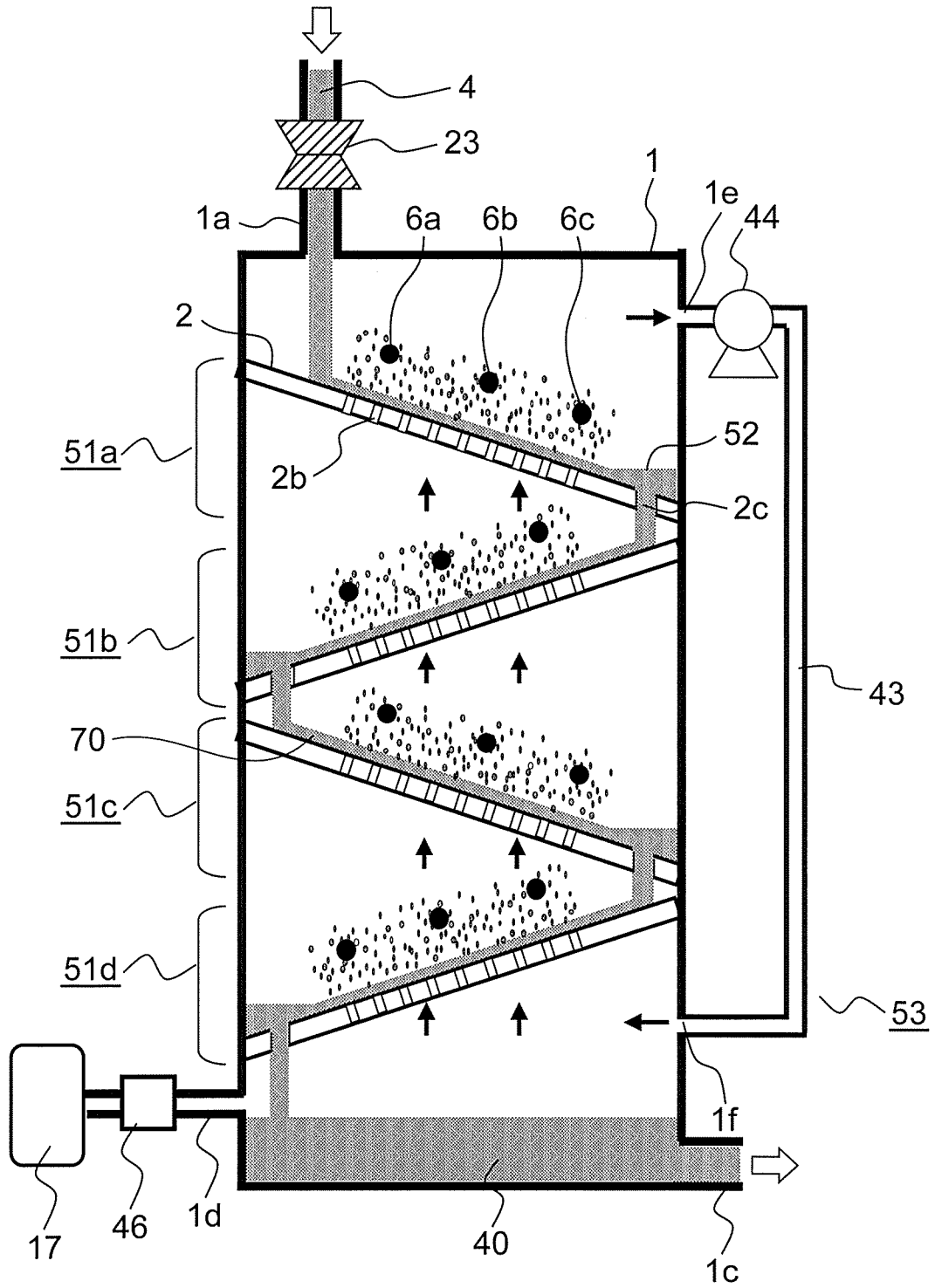


FIG. 26

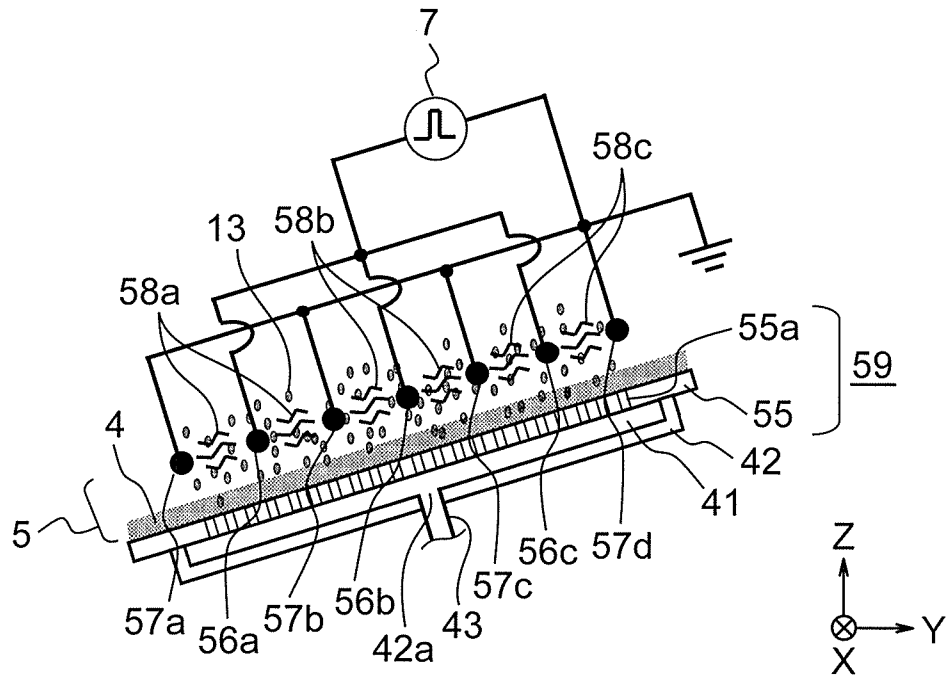


FIG. 27

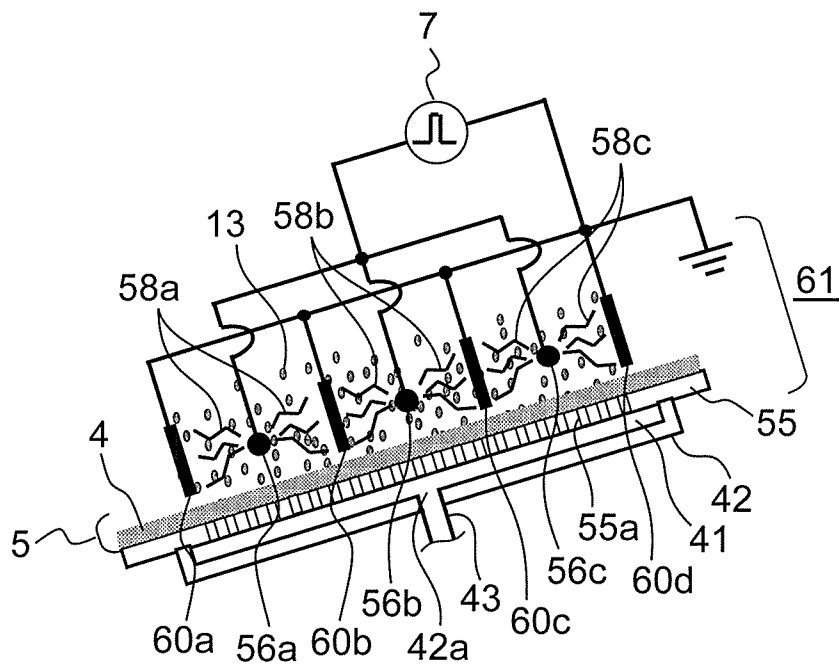


FIG. 28

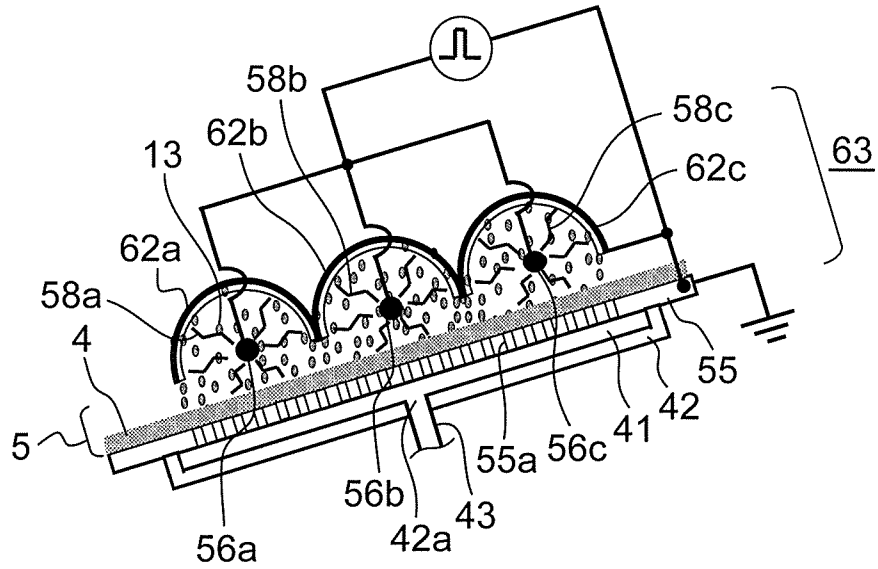


FIG. 29

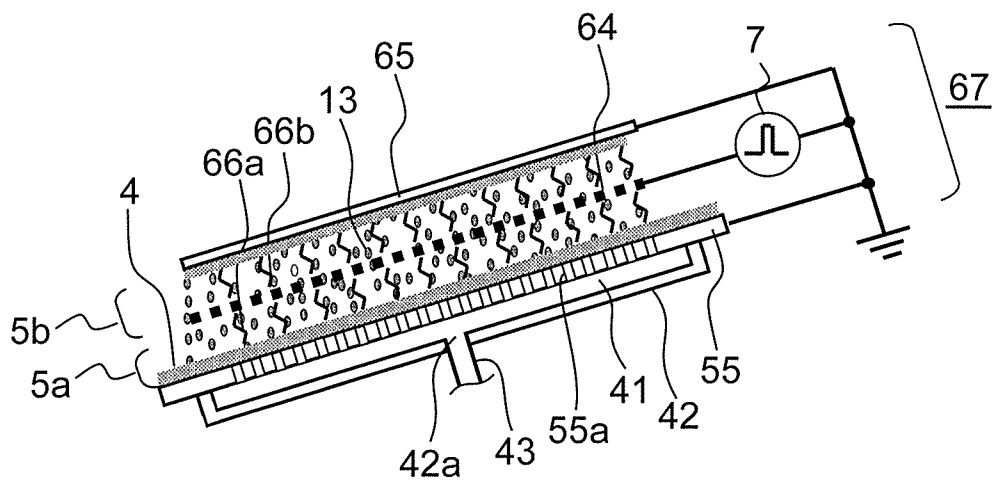


FIG. 30

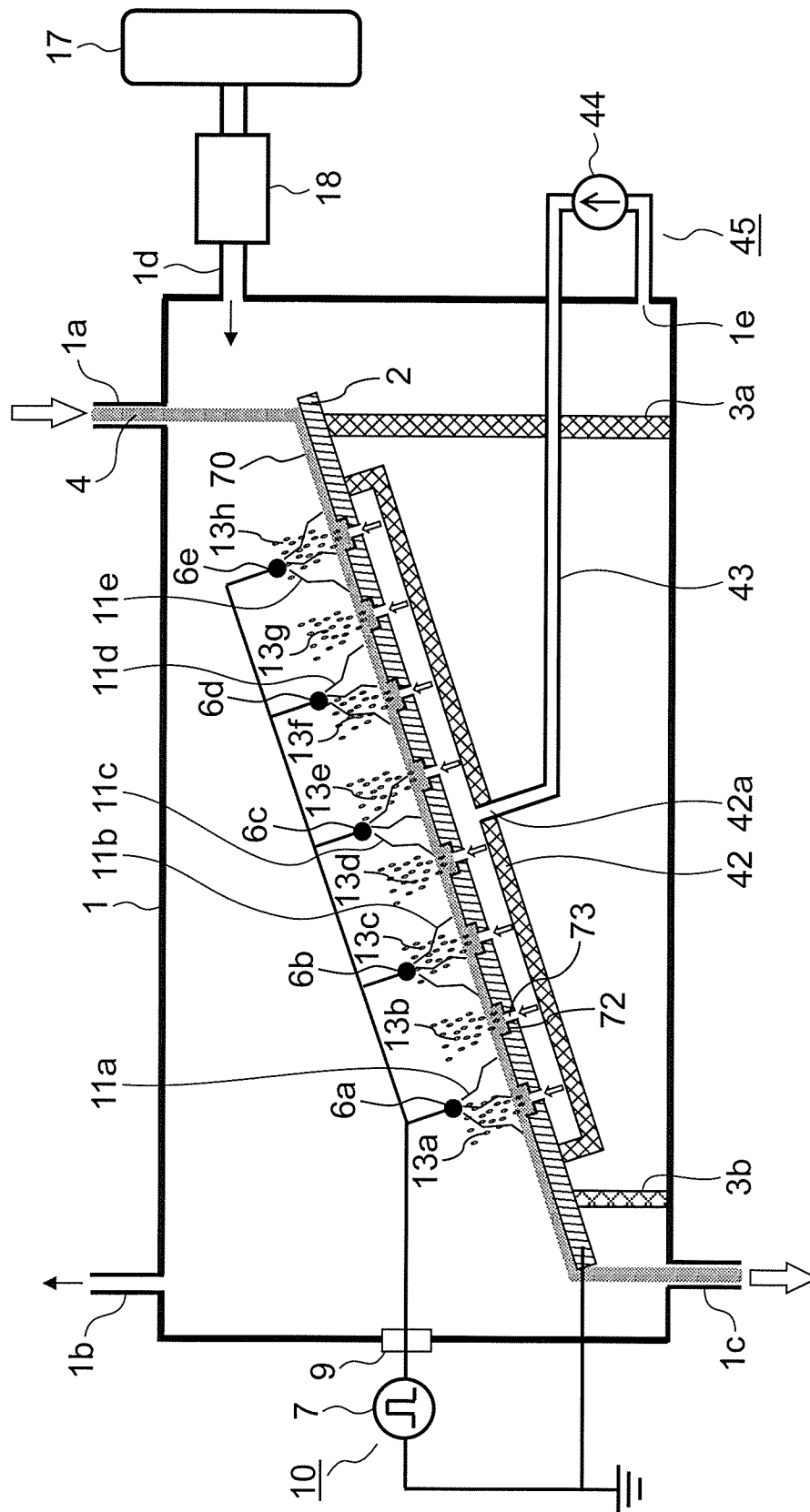


FIG. 31

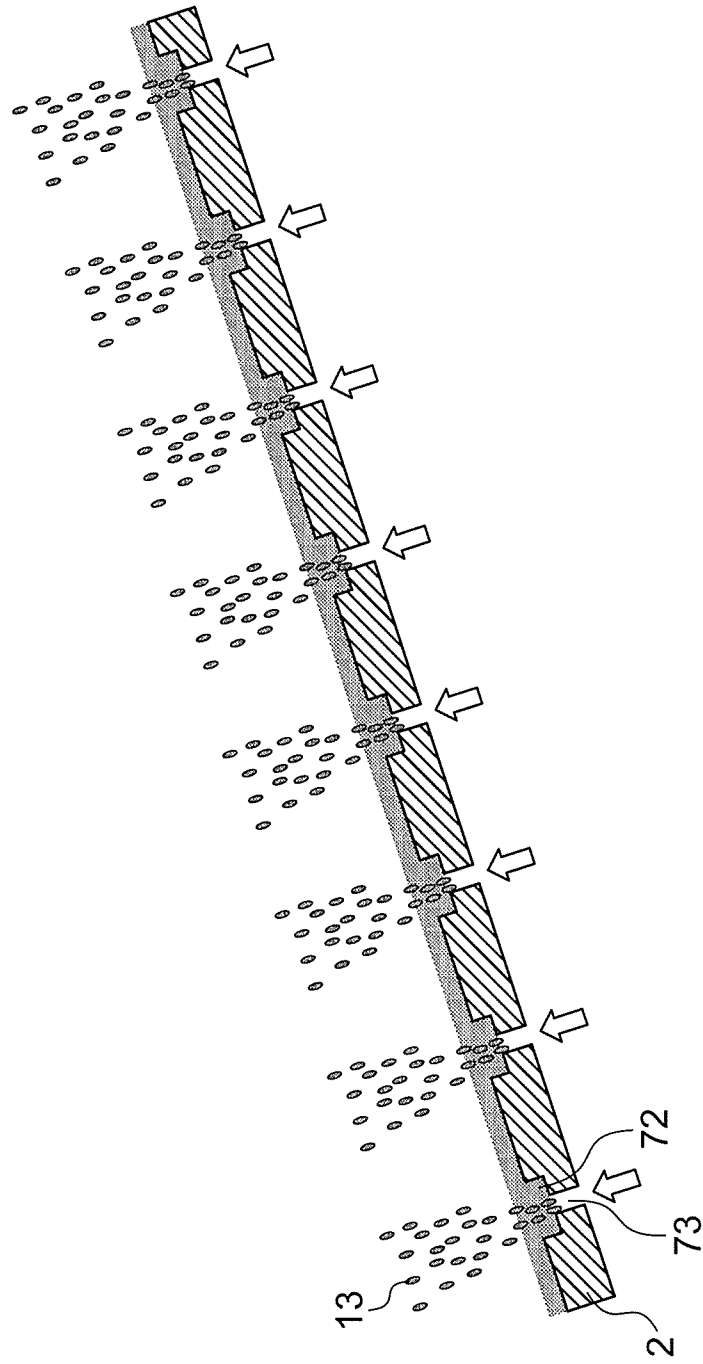


FIG. 32

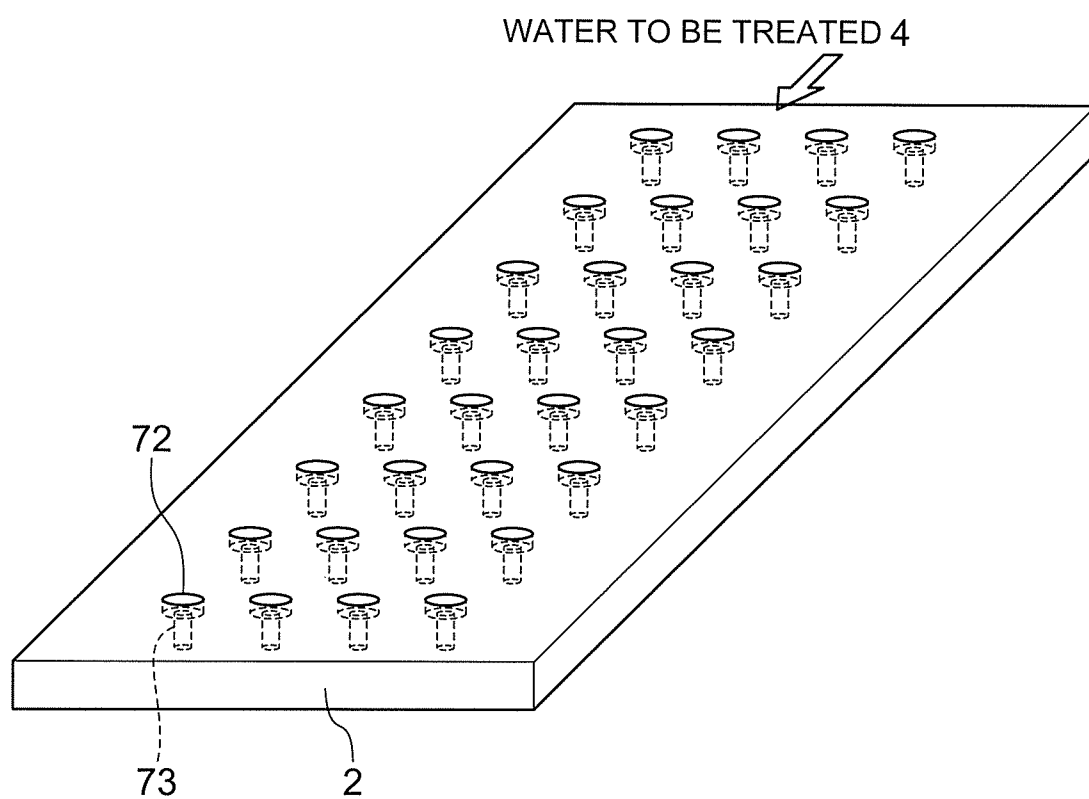


FIG. 33

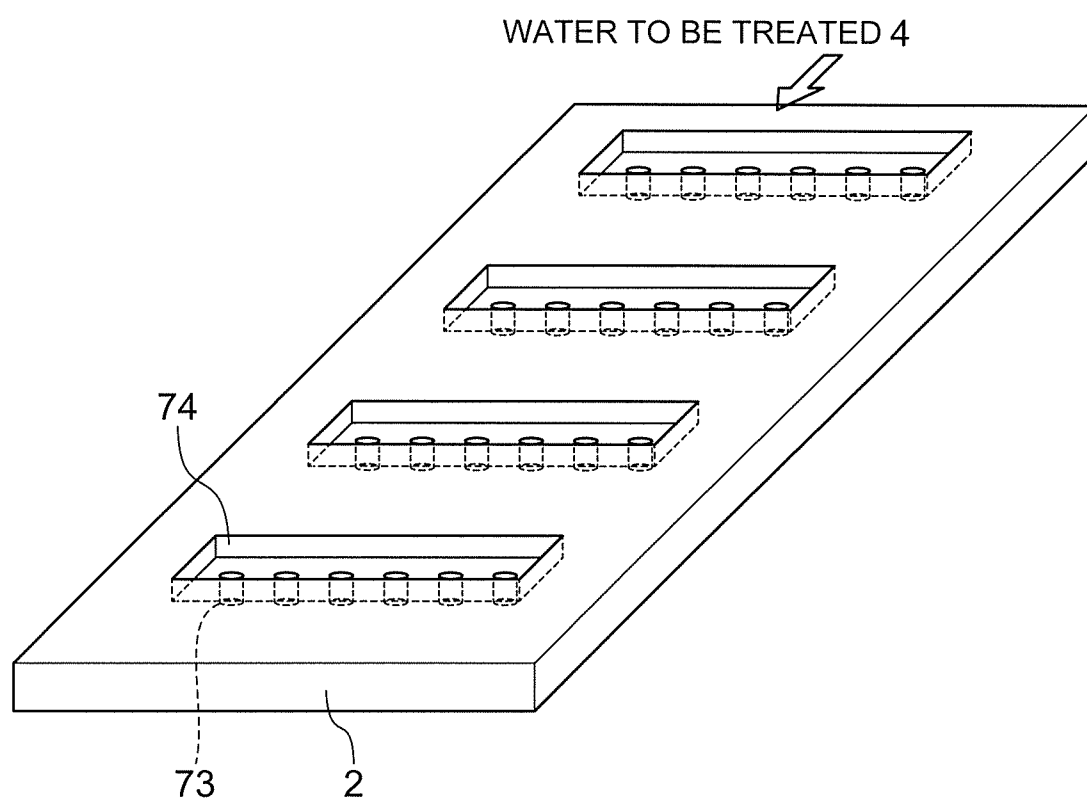


FIG. 34

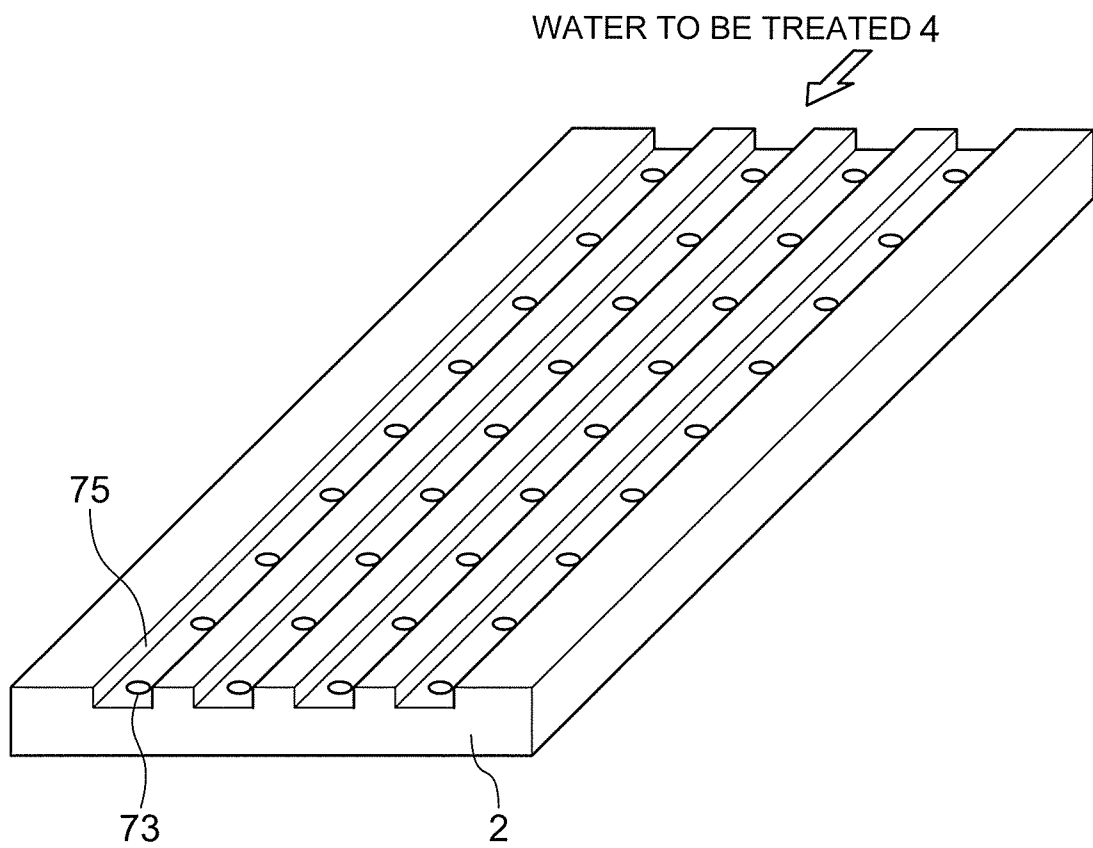


FIG. 35

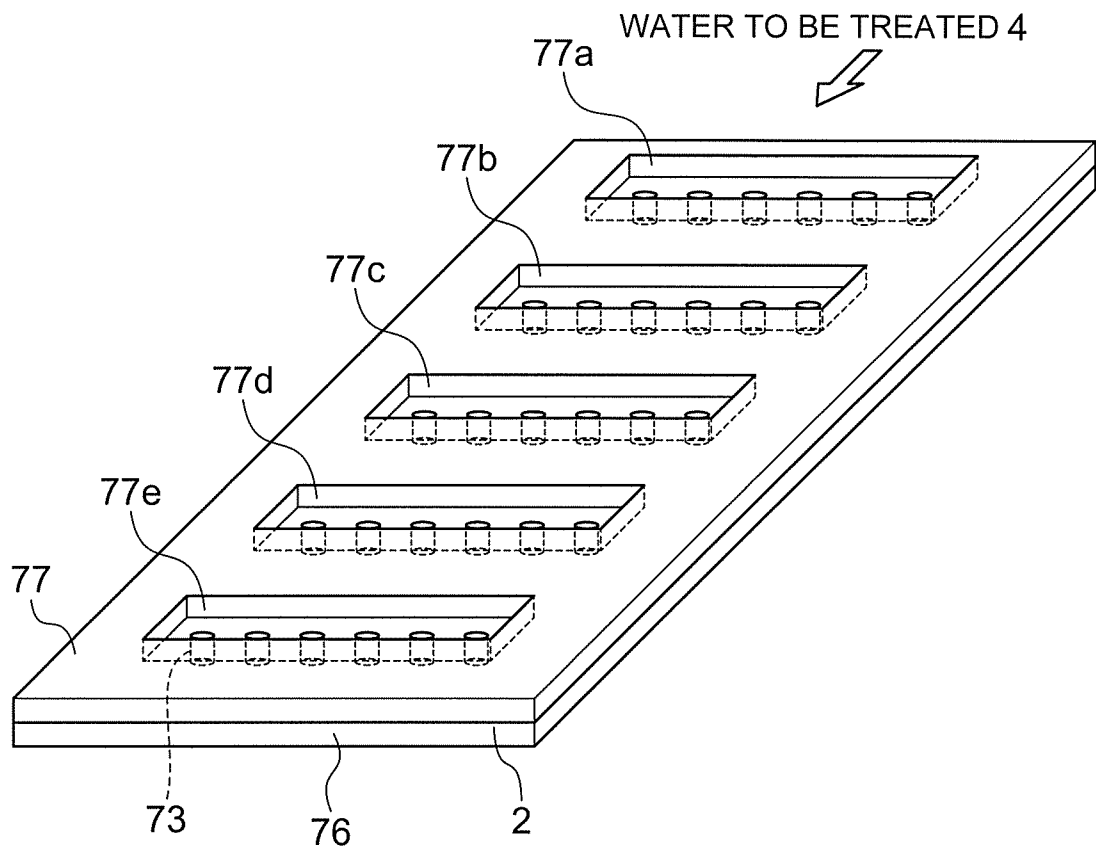


FIG. 36

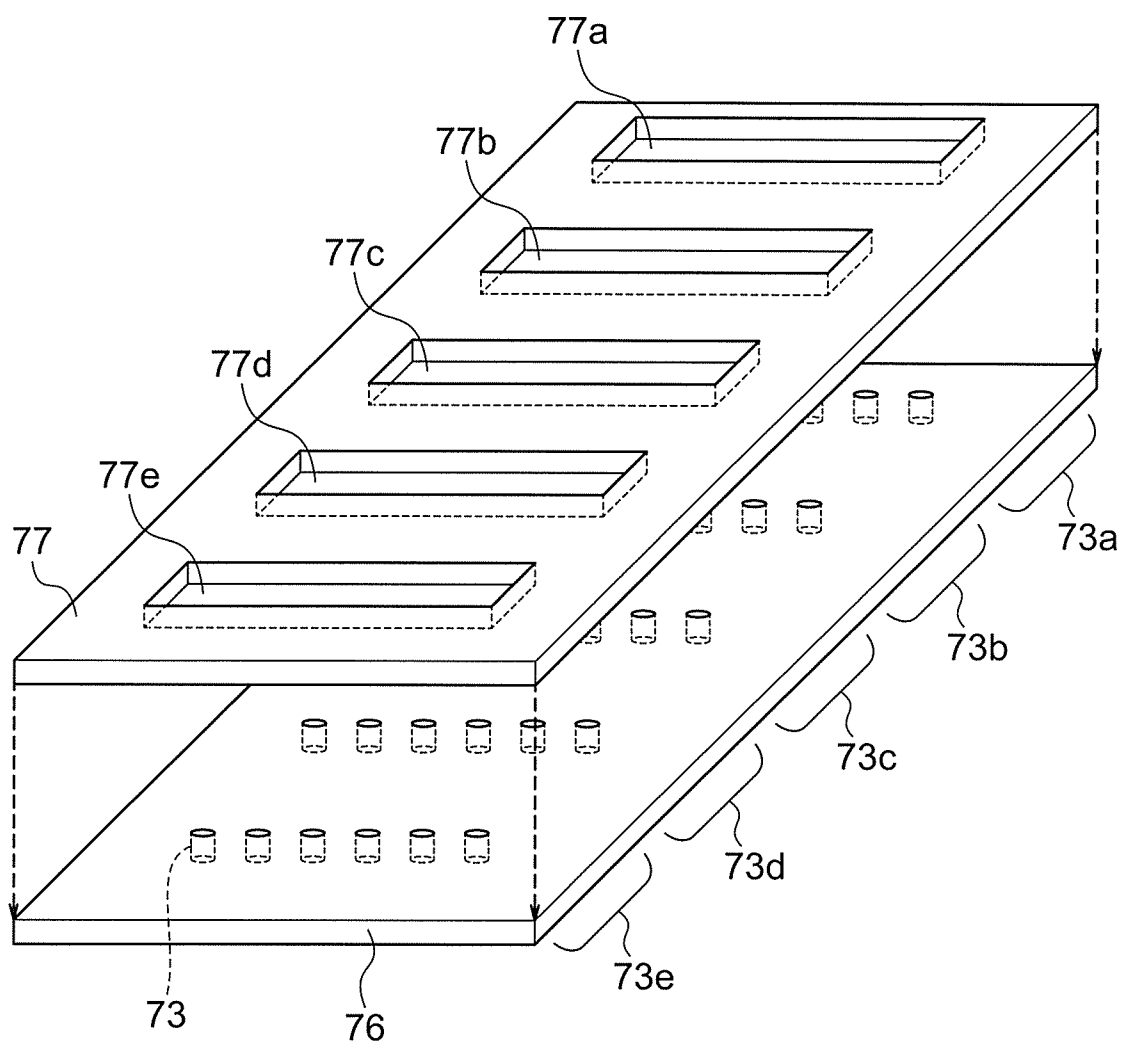


FIG. 37

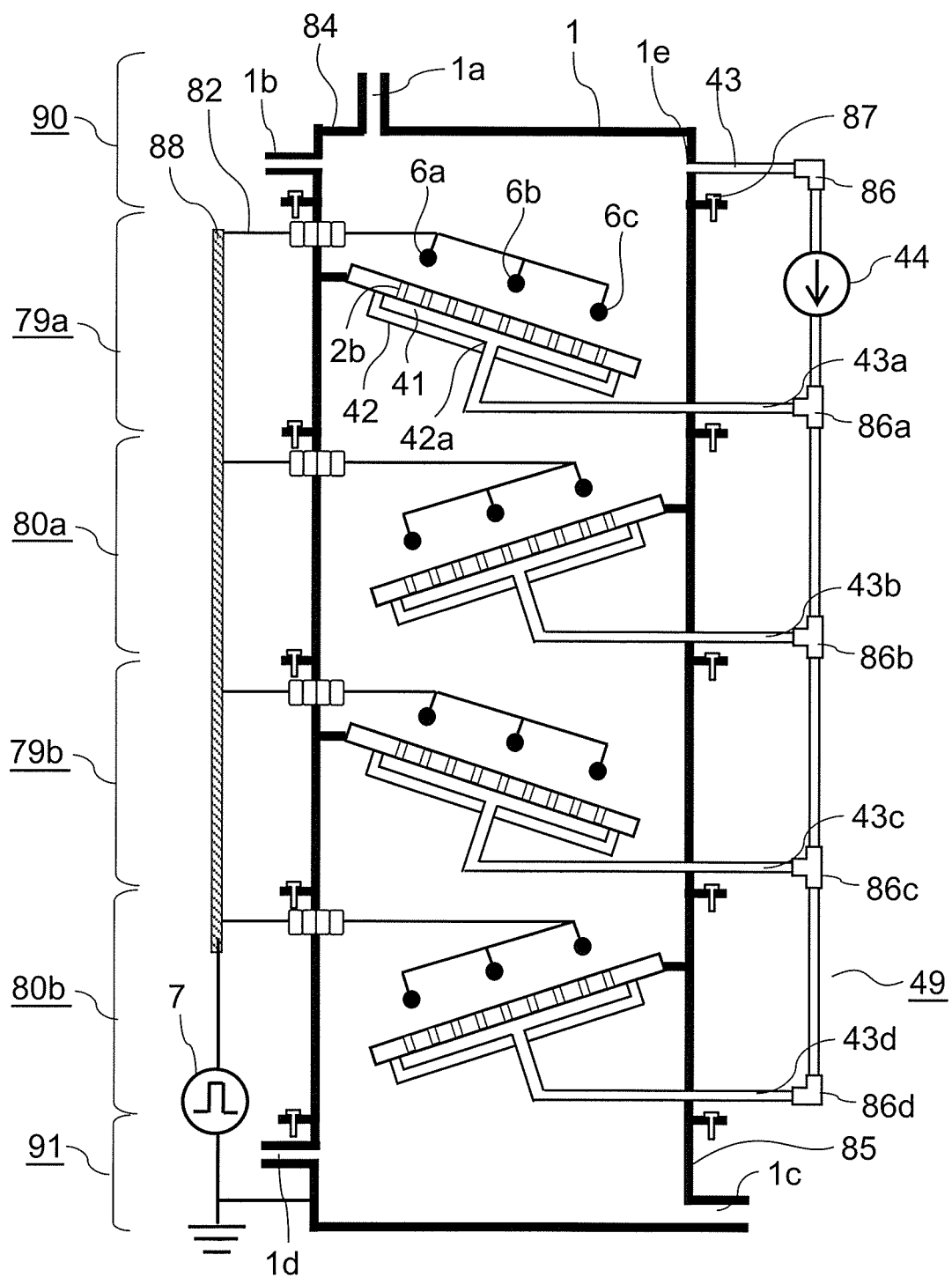


FIG. 38

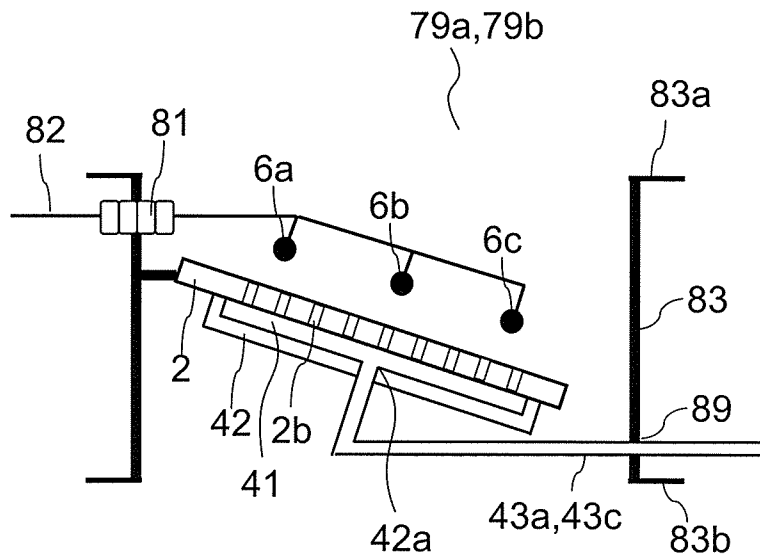


FIG. 39

